## IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A lithographic apparatus comprising: an illuminator configured to provide a beam of radiation;

a support structure configured to hold a patterning device, the patterning device configured to impart <u>a the beam of radiation</u> with a pattern in its cross-section;

a substrate table configured to hold a substrate;

a projection system configured to project the patterned beam onto a target portion of the substrate; and

a liquid supply system configured to supply a liquid to substantially only a localized area of the substrate, of the substrate table, or of both, to at least partly fill a space between the projection system and the substrate, the substrate table, or both,

wherein the localized area is less than the area of a surface of the whole substrate, and wherein the substrate table comprises a barrier configured to collect liquid, the barrier surrounding and spaced apart from the substrate and comprising a projection which projects out above an upper surface of the substrate table.

- 2. (Currently Amended) The apparatus of claim 1, wherein the barrier comprises a projection which projects out of the an upper surface of the substrate table.
- 3. (Original) The apparatus of claim 1, wherein at least a part of the barrier comprises a liquidphillic material or coating.
- 4. (Currently Amended) The apparatus of claim 1, wherein the barrier <u>further</u> comprises a groove recessed into an upper surface of the substrate table.
- 5. (Original) The apparatus of claim 4, wherein the groove is sized such that the liquid can be transported along the groove under capillary action.

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-Amendment-

- 6. (Withdrawn) The apparatus of claim 4, wherein the substrate table further comprises a chamber in liquid contact with the upper surface via the groove and wherein the groove forms a continuous loop.
- 7. (Original) The apparatus of claim 1, further comprising a low pressure supply configured to remove liquid from the barrier.
- 8. (Original) The apparatus of claim 7, wherein the low pressure supply comprises a plurality of discrete outlets.
- 9. (Original) The apparatus of claim 7, wherein the low pressure supply operates independently of the liquid supply system.
- 10. (Original) The apparatus of claim 1, further comprising a surface acoustic wave generator configured to generate surface acoustic waves in the barrier to facilitate transport of liquid along the barrier.
- 11. (Original) The apparatus of claim 10, wherein the surface acoustic wave generator comprises a piezoelectric actuator.
- 12. (Currently Amended) The apparatus of claim 1, wherein the barrier <u>further</u> comprises a groove and <u>the a-projection which projects</u> out of <u>the an-upper surface</u> of the substrate table.
- 13. (Withdrawn) The apparatus of claim 12, wherein the substrate table comprises a chamber in liquid contact with the upper surface via the groove.
- 14. (Withdrawn) The apparatus of claim 13, wherein the chamber is at least partly formed in the projection.

- 15. (Currently Amended) The apparatus of claim 1, wherein the barrier is positioned radially outwardly of a drainage ditch or <u>an additional</u> barrier, surrounding an outer peripheral edge of the substrate.
- 16. (Original) The apparatus of claim 1, wherein the barrier extends substantially around an outer edge or portion of the substrate table.
- 17. (Original) The apparatus of claim 1, wherein the barrier additionally surrounds areas of an upper surface of the substrate table which are not covered by the substrate.
- 18. (Original) The apparatus of claim 1, wherein the barrier additionally surrounds at least one sensor mounted on an upper surface of the substrate table and/or a closure member configured to seal the liquid supply system.
- 19. (Currently Amended) A device manufacturing method comprising: providing a liquid to substantially only a localized area of a substrate, of a substrate table, or of both, to at least partly fill a space between a projection system and the substrate, the substrate table, or both;

projecting a patterned beam of radiation through the liquid onto a target portion of the substrate using the projection system; and

collecting liquid with a barrier, the barrier surrounding and spaced apart from the substrate and comprising a projection which projects out above an upper surface of the substrate table,

wherein the localized area is less than the area of a surface of the whole substrate.

- 20. (Currently Amended) The method of claim 19, wherein the barrier comprises a projection which projects out of the an upper surface of the substrate table.
- 21. (Currently Amended) The method of claim 19, wherein the barrier <u>further</u> comprises a groove recessed into an upper surface of the substrate table.

- 22. (Original) The method of claim 19, further comprising removing liquid from the barrier using a low pressure supply.
- 23. (Original) The method of claim 22, wherein removing liquid from the barrier operates independently of providing the liquid.
- 24. (Original) The method of claim 19, further comprising generating surface acoustic waves in the barrier to facilitate transport of liquid along the barrier.
- 25. (Currently Amended) The method of claim 19, wherein the barrier <u>further</u> comprises a groove and <u>the a-projection which-projects</u> out of <u>the an-upper surface</u> of the substrate table.
- 26. (Withdrawn) The method of claim 25, wherein the substrate table comprises a chamber at least partly formed in the projection and in liquid contact with the upper surface via the groove.
- 27. (Currently Amended) The method of claim 19, further comprising removing liquid using a drainage ditch or <u>an additional</u> barrier, surrounding an outer peripheral edge of the substrate and positioned radially inwardly of the barrier.
  - 28. (New) A lithographic apparatus comprising:
- a support structure configured to hold a patterning device, the patterning device configured to impart a beam of radiation with a pattern in its cross-section;
  - a substrate table configured to hold a substrate;
- a projection system configured to project the patterned beam onto a target portion of the substrate; and
- a liquid supply system configured to supply a liquid to substantially only a localized area of the substrate, of the substrate table, or of both, to at least partly fill a space between the projection system and the substrate, the substrate table, or both,

wherein the localized area is less than the area of a surface of the whole substrate, and

wherein the substrate table comprises a first barrier configured to collect liquid, the first barrier surrounding and spaced apart from the substrate and positioned radially outwardly of a second barrier surrounding an outer peripheral edge of the substrate.

- 29. (New) The apparatus of claim 28, wherein at least a part of the first barrier comprises a liquidphillic material or coating.
- 30. (New) The apparatus of claim 28, wherein the first barrier comprises a groove recessed into an upper surface of the substrate table.
- 31. (New Withdrawn) The apparatus of claim 30, wherein the substrate table further comprises a chamber in liquid contact with an upper surface of the substrate table via the groove and wherein the groove forms a continuous loop.
- 32. (New) The apparatus of claim 28, wherein the first barrier comprises a projection which projects out above an upper surface of the substrate table.
- 33. (New Withdrawn) The apparatus of claim 32, wherein the substrate table further comprises a chamber at least partly formed in the projection, the chamber in liquid contact with an upper surface of the substrate.
- 34. (New) The apparatus of claim 28, further comprising a low pressure supply configured to remove liquid from the first barrier.
- 35. (New) The apparatus of claim 28, wherein the first barrier extends substantially around an outer edge or portion of the substrate table.
- 36. (New) The apparatus of claim 28, wherein the first barrier additionally surrounds a sensor mounted on an upper surface of the substrate table and/or a closure member configured to seal the liquid supply system.